

EURLINGS et al. -- 10/680,413  
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IN THE ABSTRACT:

The abstract is amended as follows:

A lithographic projection system has an illumination system. A plurality of directing elements direct different sub-beams of an incident beam into predetermined directions. By using re-directing optics any desired angular intensity distribution of the ~~projection~~ beam can be produced. The illumination system includes a setting device that includes a reflector plate that supports reflectors. The reflectors are resiliently supported on the reflector plate. At least one aperture in the reflector plate is associated with each reflector. A setting plate includes at least one pin associated with each reflector. The pins of the setting plate are insertable into the apertures of the reflector plate. Each pin or pins engages its associated reflector to control the orientation of the associated reflector by rotation about two axes substantially perpendicular to the optical axis of the associated reflector.